

L Number	Hits	Search Text	DB	Time stamp
1	3	6752911.pn. or 6350961.pn. or 6129856.pn.	USPAT; US-PGPUB	2004/09/21 13:50
2	3	(6752911.pn. or 6350961.pn. or 6129856.pn.) and (hollow near2 (cathode or electrode))	USPAT; US-PGPUB	2004/09/21 13:50
3	11	(Jung.in. or Klages.in. or Fraunhofer.as.) and ((hollow adj cathode) with (band or moving or substrate or running) with (coat\$3 or deposit\$3 or film or layer))	USPAT; US-PGPUB	2004/09/21 13:59
4	20	(Jung.in. or Klages.in. or Fraunhofer.as.) and (hollow adj cathode)	USPAT; US-PGPUB	2004/09/21 13:58
5	9	((Jung.in. or Klages.in. or Fraunhofer.as.) and (hollow adj cathode)) not ((Jung.in. or Klages.in. or Fraunhofer.as.) and ((hollow adj cathode) with (band or moving or substrate or running) with (coat\$3 or deposit\$3 or film or layer)))	USPAT; US-PGPUB	2004/09/21 13:58
6	43	(Jung or Klages or Fraunhofer) and (hollow adj cathode)	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 13:59
7	16	(Jung.in. or Klages.in. or Fraunhofer.as.) and ((hollow adj cathode) with (band or moving or substrate or running) with (coat\$3 or deposit\$3 or film or layer))	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 14:04
8	27	((Jung or Klages or Fraunhofer) and (hollow adj cathode)) not ((Jung.in. or Klages.in. or Fraunhofer.as.) and ((hollow adj cathode) with (band or moving or substrate or running) with (coat\$3 or deposit\$3 or film or layer)))	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 14:07
9	1753	(427/569,575,488).CCLS.	USPAT; US-PGPUB	2004/09/21 14:07
10	652	(427/209).CCLS.	USPAT; US-PGPUB	2004/09/21 14:08
11	414	(427/237).CCLS.	USPAT; US-PGPUB	2004/09/21 14:08
12	2187	(427/248.1,255.5).CCLS.	USPAT; US-PGPUB	2004/09/21 14:08
13	899	(427/405).CCLS.	USPAT; US-PGPUB	2004/09/21 14:08
14	3719	(118/718,719,723R,723E,723MW).CCLS.	USPAT; US-PGPUB	2004/09/21 14:08
15	8838	((427/569,575,488).CCLS.) ((427/209).CCLS.) ((427/237).CCLS.) ((427/248.1,255.5).CCLS.) ((427/405).CCLS.) ((118/718,719,723R,723E,723MW).CCLS.)	USPAT; US-PGPUB	2004/09/21 14:10
16	107	((427/569,575,488).CCLS.) and (hollow near2 (electrode or cathode))	USPAT; US-PGPUB	2004/09/21 14:26
17	0	((427/209).CCLS.) and (hollow near2 (electrode or cathode))	USPAT; US-PGPUB	2004/09/21 14:26
18	16	((427/237).CCLS.) and (hollow near2 (electrode or cathode))	USPAT; US-PGPUB	2004/09/21 14:30
19	29	((427/248.1,255.5).CCLS.) and (hollow near2 (electrode or cathode))	USPAT; US-PGPUB	2004/09/21 14:34
20	2	((427/405).CCLS.) and (hollow near2 (electrode or cathode))	USPAT; US-PGPUB	2004/09/21 14:35
21	162	((118/718,719,723R,723E,723MW).CCLS.) and (hollow near2 (electrode or cathode))	USPAT; US-PGPUB	2004/09/21 14:35

22	125	((118/718,719,723R,723E,723MW).CCLS.) and (hollow near2 (electrode or cathode))) not (((427/569,575,488).CCLS.) and (hollow near2 (electrode or cathode))) or (((427/209).CCLS.) and (hollow near2 (electrode or cathode))) or (((427/237).CCLS.) and (hollow near2 (electrode or cathode))) or (((427/248.1,255.5).CCLS.) and (hollow near2 (electrode or cathode))) or (((427/405).CCLS.) and (hollow near2 (electrode or cathode))))	USPAT; US-PGPUB	2004/09/21 14:55
23	24	(band or member or substrate or base or metal\$5 or conductive) near3 (function or "is" or form) near3 (hollow near2 cathode)	USPAT; US-PGPUB	2004/09/21 15:05
24	7	(band or member or substrate or base or metal\$5 or conductive) near3 (function or "is" or form) near3 (hollow near2 cathode)	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 15:07
25	155	(coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 15:21
26	153	((coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)) not ((band or member or substrate or base or metal\$5 or conductive) near3 (function or "is" or form) near3 (hollow near2 cathode))	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 15:08
27	250	(coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)	USPAT; US-PGPUB	2004/09/21 15:40
28	32	((coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)) and (((427/569,575,488).CCLS.) ((427/209).CCLS.) ((427/237).CCLS.) ((427/248.1,255.5).CCLS.) ((427/405).CCLS.) ((118/718,719,723R,723E,723MW).CCLS.)))	USPAT; US-PGPUB	2004/09/21 15:21
29	38	((coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)) and ((hollow near2 cathode) near3 (treated or substrate or base or workpiece or band or running))	USPAT; US-PGPUB	2004/09/21 15:29
30	2	"6326373"	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 15:30
31	3	"26373"	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 15:30
32	2	"63026373"	EPO; JPO; DERWENT; IBM_TDB	2004/09/21 15:31
33	188	((coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)) not (((coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)) and (((427/569,575,488).CCLS.) ((427/209).CCLS.) ((427/237).CCLS.) ((427/248.1,255.5).CCLS.) ((427/405).CCLS.) ((118/718,719,723R,723E,723MW).CCLS.))) or (((coat\$3 or deposit\$4 or \$4CVD or film or layer) near3 (hollow near2 cathode)) and ((hollow near2 cathode) near3 (treated or substrate or base or workpiece or band or running))))	USPAT; US-PGPUB	2004/09/21 15:31
34	90	(coat\$3 or deposit\$4 or \$4CVD or film or layer) with (hollow near2 cathode) near4 (surface or inside or interior or wall)	USPAT; US-PGPUB	2004/09/21 15:42

35	8	((coat\$3 or deposit\$4 or \$4CVD or film or layer) with (hollow near2 cathode) near4 (surface or inside or interior or wall)) and (((427/569,575,488).CCLS.) ((427/209).CCLS.) ((427/237).CCLS.) ((427/248.1,255.5).CCLS.) ((427/405).CCLS.) ((118/718,719,723R,723E,723MW).CCLS.)))	USPAT; US-PGPUB	2004/09/21 15:41
36	52	(coat\$3 or deposit\$4 or \$4CVD or film or layer) with (hollow near2 cathode) near2 (surface or inside or interior or wall)	USPAT; US-PGPUB	2004/09/21 15:46
37	48	((coat\$3 or deposit\$4 or \$4CVD or film or layer) with (hollow near2 cathode) near2 (surface or inside or interior or wall)) not (((coat\$3 or deposit\$4 or \$4CVD or film or layer) with (hollow near2 cathode) near4 (surface or inside or interior or wall)) and (((427/569,575,488).CCLS.) ((427/209).CCLS.) ((427/237).CCLS.) ((427/248.1,255.5).CCLS.) ((427/405).CCLS.) ((118/718,719,723R,723E,723MW).CCLS.)))	USPAT; US-PGPUB	2004/09/21 15:43
38	23	(coat\$3 or deposit\$4 or \$4CVD or film or layer) with (hollow near2 cathode) near2 (surface or inside or interior or wall)	EPO; JPO; DERWENT; IBM TDB	2004/09/21 15:47